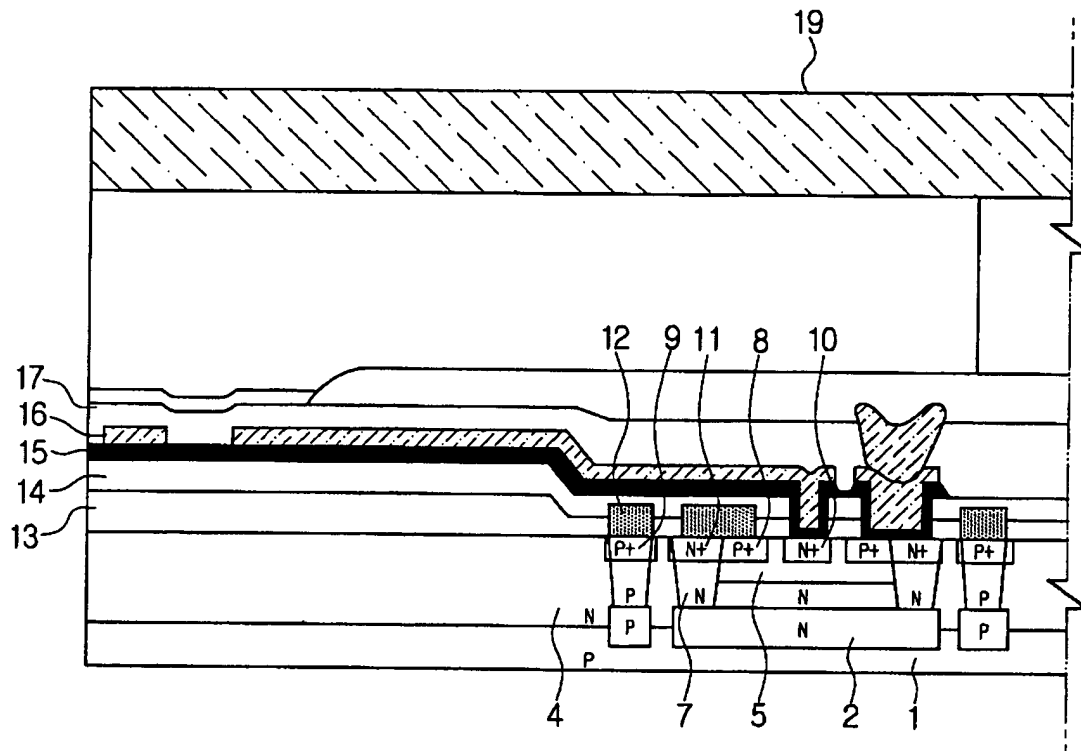


FIG.1 PRIOR ART



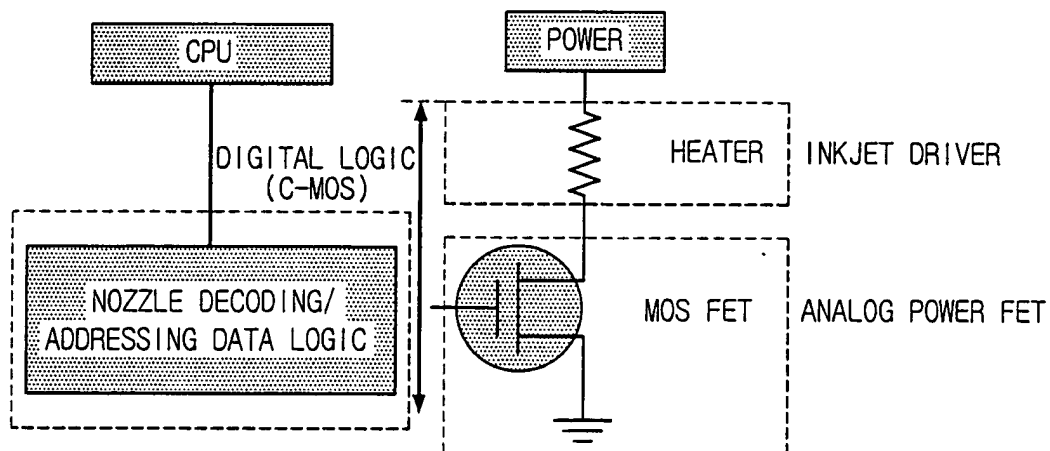


FIG. 4

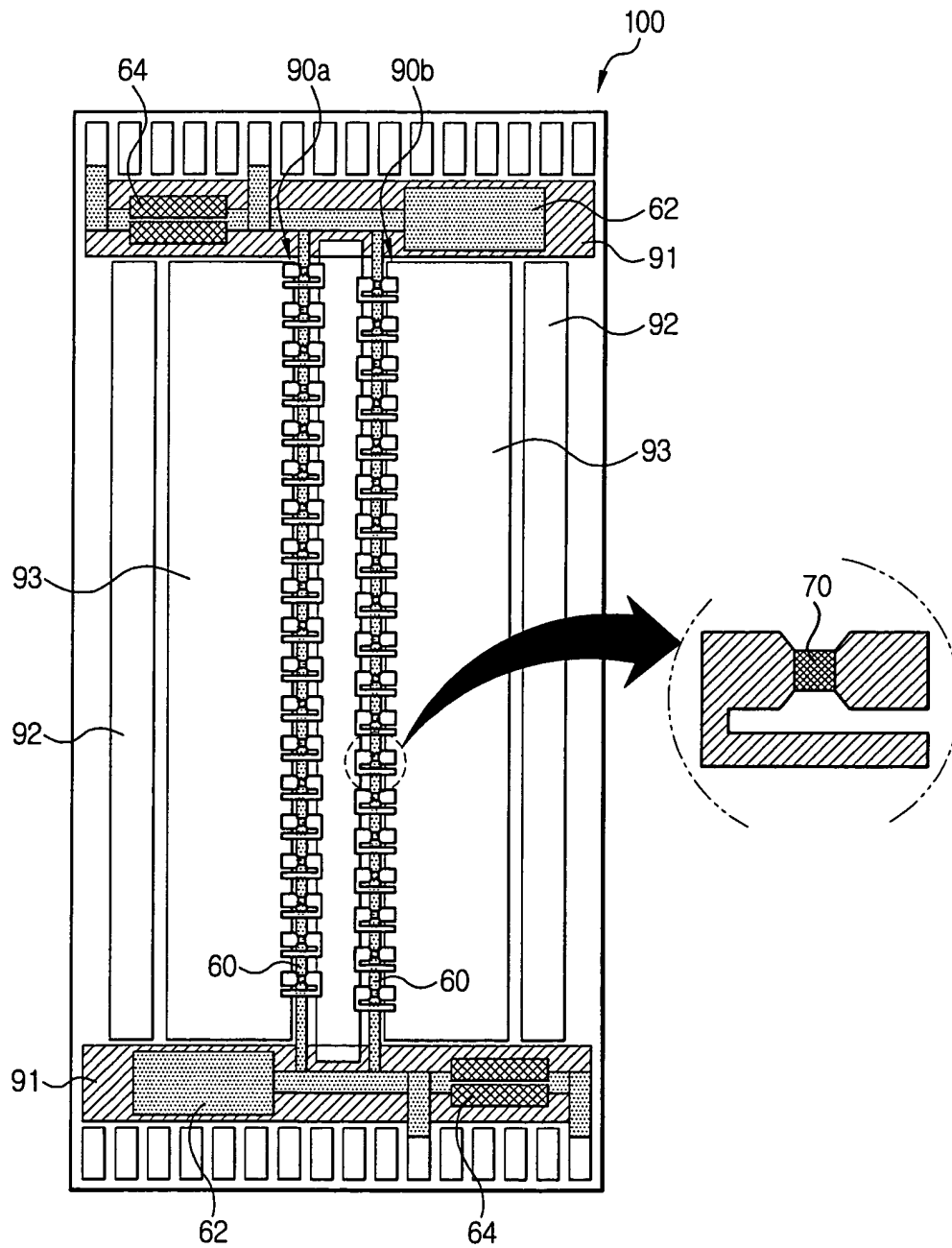


FIG. 5A

-Starting material(pwp18675) -Initial oxidation -1st SiN deposition

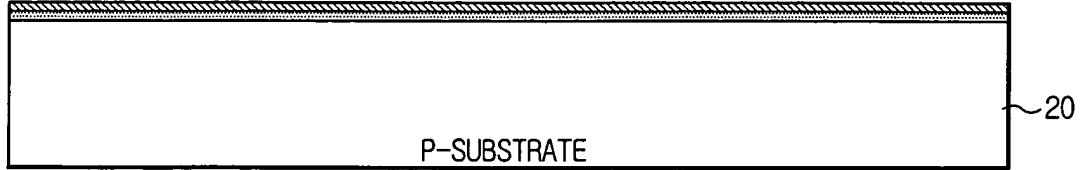


FIG. 5B

-PWELL photo -SiN etch -NEWLL implant

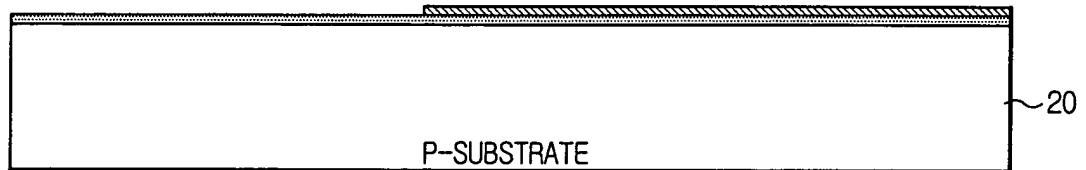


FIG. 5C

-NWELL oxidation SiN remove -PWELL implant -WDR(Well Drive In)

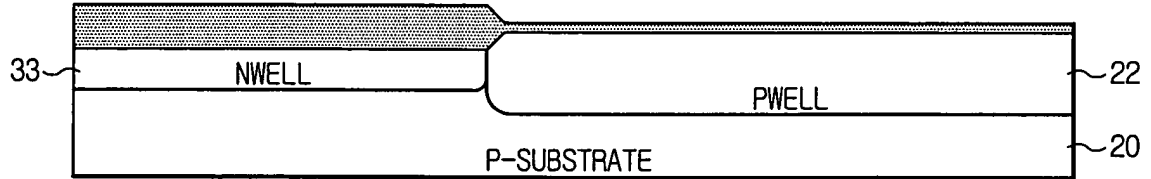


FIG. 5D

-Oxide remove -2nd oxidation -2nd SiN deposition

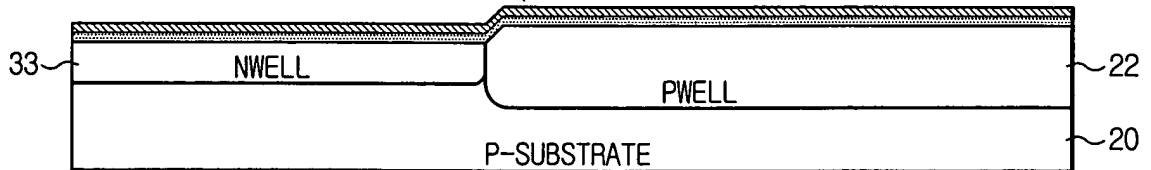


FIG. 5E

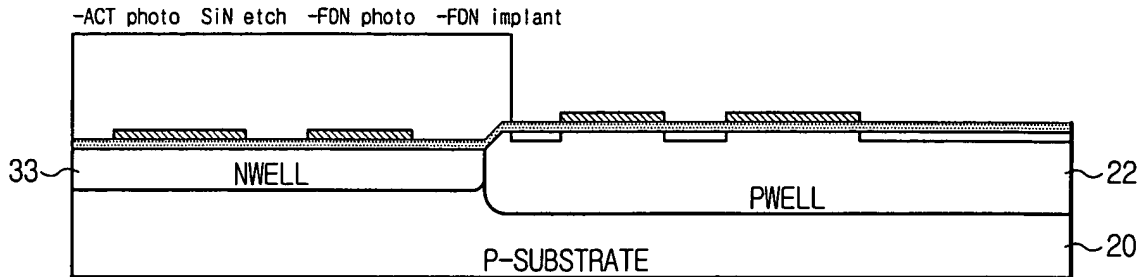


FIG. 5F

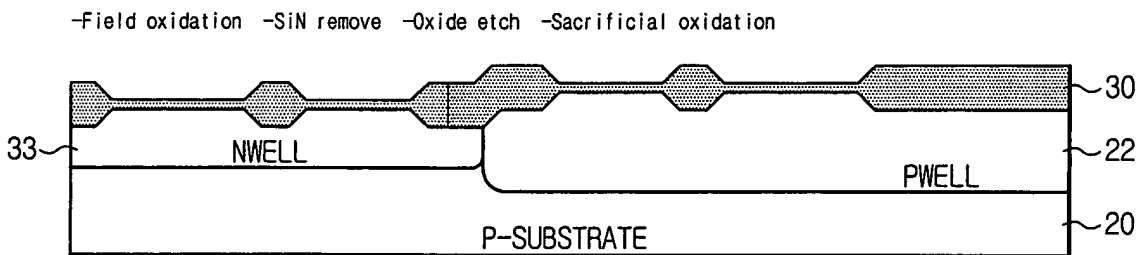


FIG. 5G

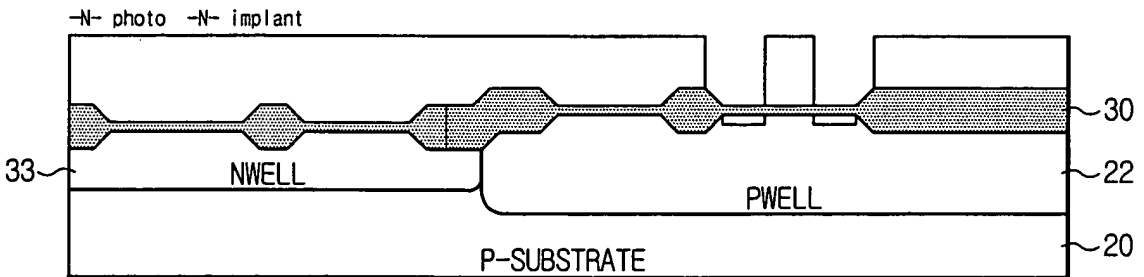


FIG. 5H

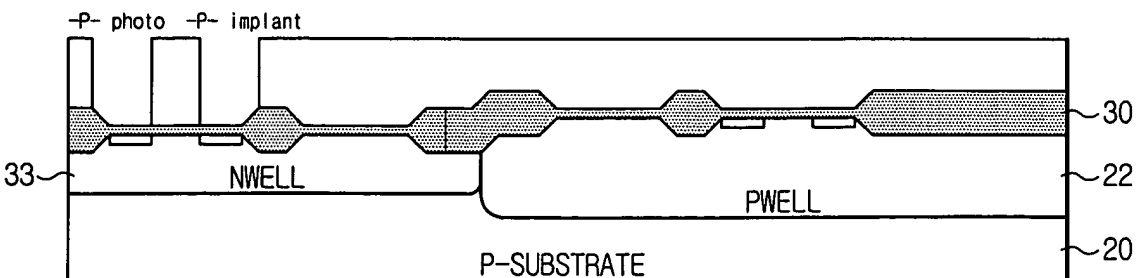


FIG. 5I

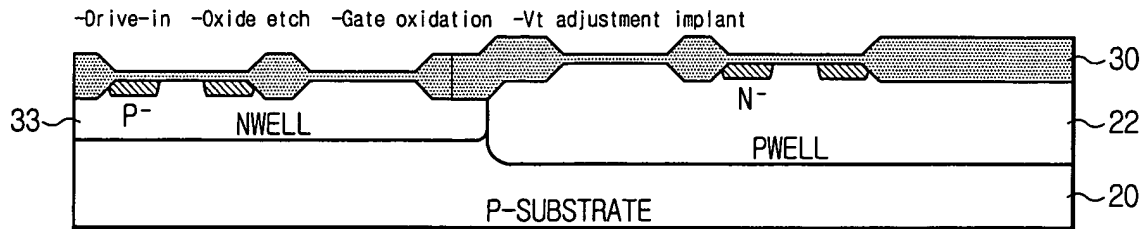


FIG. 5J

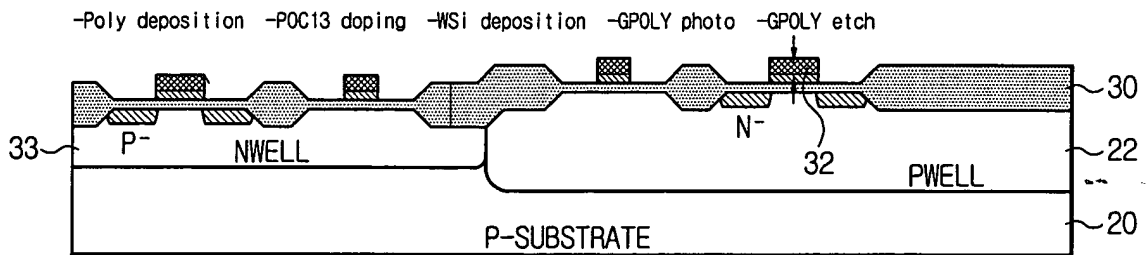


FIG. 5K

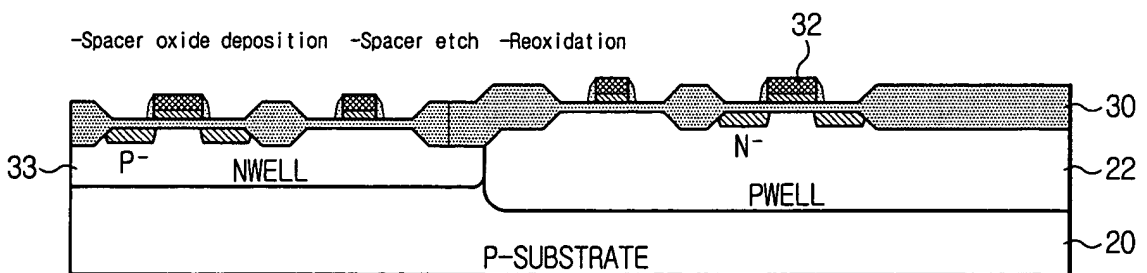


FIG. 5L

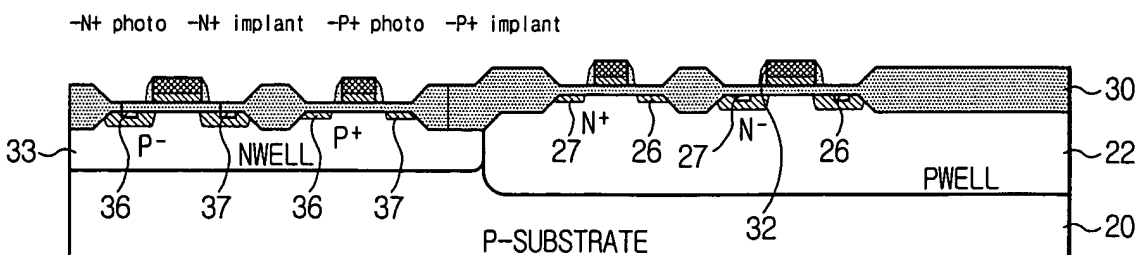


FIG. 5M

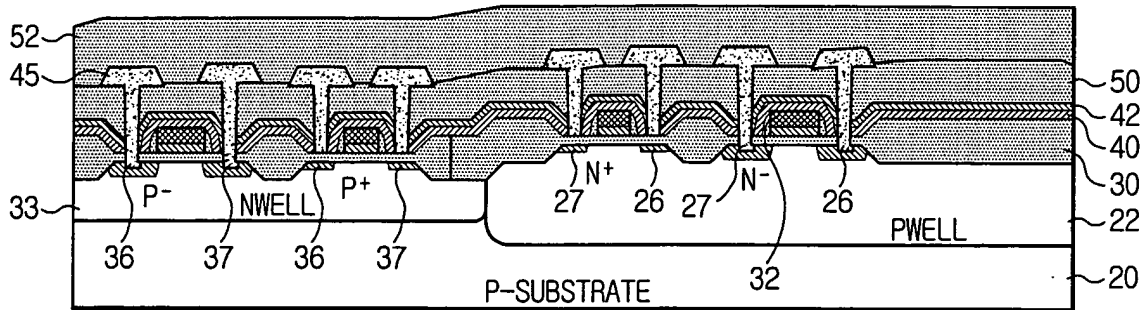


FIG. 5N

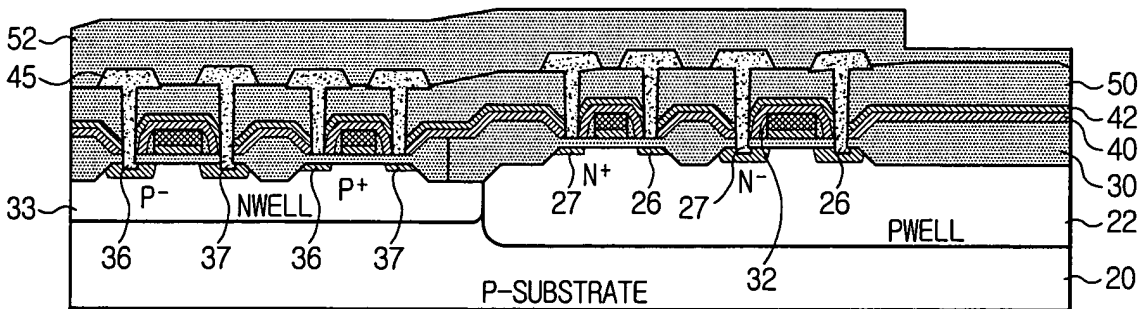
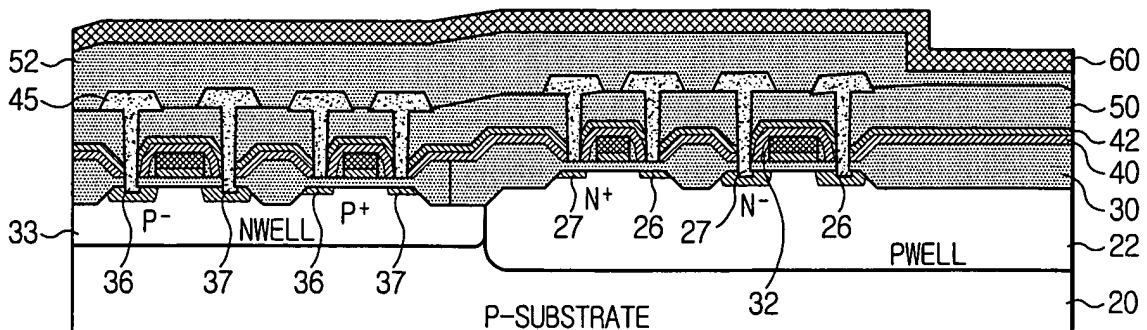


FIG. 5O



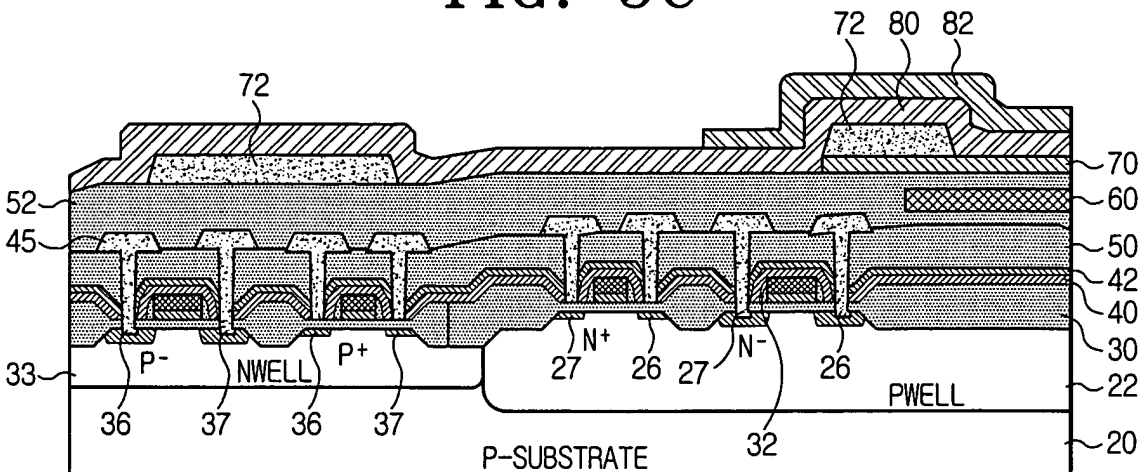


FIG. 6

